



PRESS RELEASE

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Intelligent Micro Patterning Provides SF-100 XTREME to the Biodesign Institute at Arizona State University

Intelligent Micro Patterning, LLC, St. Petersburg, Florida, announced the installation of an SF-100 XTREME maskless lithography system at the Biodesign Institute at Arizona State University, Tempe, AZ. The SF-100 XTREME provides for features as small as 1 micron in size, advancing research in such fields as nanotechnology, biotechnology and microfluidics. The SF-100 XTREME is a unique, maskless photolithography system that utilizes patented Smart Filter technology, licensed by Intelligent Micro Patterning, LLC from the University of South Florida. Smart Filter technology incorporates proprietary, cutting-edge, micro-optical techniques to rapidly project master images directly onto diverse substrate materials.

Dr. Jay Sasserath, the company's Chief Executive officer, said, "The SF-100 XTREME was developed with researchers at ASU for use in their lab-on-a-chip single-cell physiological analysis program. This co-development program was a huge success and both of our teams will benefit from the result. Since there are multiple SF-100 systems at the Biodesign Institute, we expect that the addition of the recent SF-100 XTREME will allow us to continue our strong relationship in years to come."

The institute's Center for Ecogenomics will utilize the system in their research on human cancer and marine microbial communities for photolithography on versatile substrates (standard/non-standard, flat/non-flat, thin/thick, different shapes) for biological cell trapping and physiological sensor deposition, selective local structure patterning, contact mask fabrication and UV curable sensor micropatterning.

Dr. Deirdre Meldrum, director of the Center for Ecogenomics, said, "The reason we purchased this tool is to make testing of our new concepts and designs easier, quicker and more cost effective. The SF-100 XTREME will expedite process characterization and optimization, reduce development time and cost, and allow us to identify the process window for new photosensitive materials. This system will ultimately have a significant positive impact on our chip fabrication results and production yields."

For more information, see the Intelligent Micro Patterning Website at www.intelligentmp.com